Growth Behavior and Film Properties of Titanium Dioxide by Plasma-Enhanced Atomic Layer Deposition with Discrete Feeding Method

Heungseop Song, Donghyuk Shin, Ji-eun Jung, Heungsoo Park* and Dae-Hong Ko*

Department of Materials Science and Engineering, Yonsei University, Seoul 03722, Korea

E-mail : hs1213.song@yonsei.ac.kr

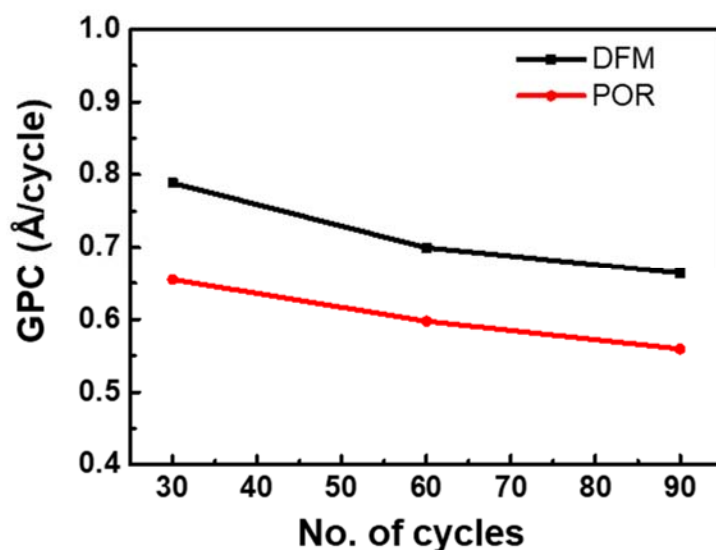

Fig.1 Growth-per-cycle comparison between reference group and DFM group

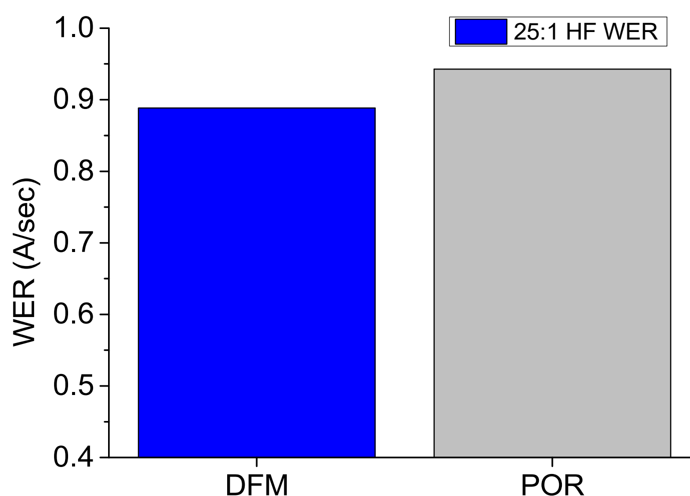

Fig.2 Wet etch rate test results using 25 :1 HF chemical at 23℃